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T-035 P02/21 U-168

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U.S.S.N. 10/050,322

JUL 28 2004

OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Tsai et al.

Group Art Unit: 1756

Serial No.: 10/050,322

Examiner: Kathleen Duda

Filed: 01/15/2002

In Response to Office Action

Dated: 05/28/2004

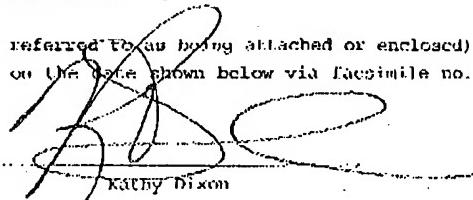
For: A BI-LAYER PHOTORESIST DRY DEVELOPMENT AND  
REACTIVE ION ETCH METHOD

Attorney Docket No.: 67,200-613

Certificate of Facsimile Transmission

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the United States Patent Office on the date shown below via facsimile no. (703) 672-9311.

Date: July 28/04

  
Kathy Dixon

REQUEST FOR RECONSIDERATION

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Va 22313-1450

Dear Sir:

In response to an Office Action mailed 05/28/2004 please consider the following remarks and allow entry of the proposed amendments to either place the application in condition for allowance or in better form for Appeal.